

FORM PTO-1449

U.S. DEPARTMENT OF COMMERCE
PATENT AND TRADEMARK OFFICEATTY. DOCKET NO.
ASMJP.104DV1APPLICATION NO.
10708,624INFORMATION DISCLOSURE STATEMENT
BY APPLICANT

(USE SEVERAL SHEETS IF NECESSARY)

APPLICANT
Akira SHIMIZU, et al.FILING DATE
November 12, 2003GROUP
1725

U.S. PATENT DOCUMENTS

EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE (IF APPROPRIATE)
M	1.	4,804,431	02/14/89	Aaron RIBNER			
H	2.	4,910,042	03/20/90	Jiri HOKYNAR			
A	3.	5,023,056	06/11/91	Monti E. AKLUF, et al.			
M	4.	5,489,362	02/06/96	Heinz STEINHARDT, et al.			
M	5.	5,795,831	08/18/98	Izumi NAKAYAMA, et al.			
r	6.	5,954,911	09/21/99	Eric J. BERGMAN, et al.			

FOREIGN PATENT DOCUMENTS

EXAMINER INITIAL		DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
							YES	NO

EXAMINER
INITIAL

OTHER DOCUMENTS (INCLUDING AUTHOR, TITLE, DATE, PERTINENT PAGES, ETC.)

M	7.	D.F. Weston, et al. HF vapor phase etching (HF/VPE): Production viability for semiconductor manufacturing and reaction model, J. Vac. Scie. Technol., 17(1) Jan./Feb. 1980, 1980 American Vacuum Society, pp. 466-468.					

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091604

EXAMINER

M. Asch

DATE CONSIDERED

3-5-03

*EXAMINER: INITIAL IF CITATION CONSIDERED, WHETHER OR NOT CITATION IS IN CONFORMANCE WITH MPEP 609; DRAW LINE THROUGH CITATION IF NOT IN CONFORMANCE AND NOT CONSIDERED, INCLUDE COPY OF THIS FORM WITH NEXT COMMUNICATION TO APPLICANT.